

Docket No.: M4065.0693/P693-A
(PATENT)

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Patent Application of:

John T. Moore

Divisional of Application No.

09/779,983 filed February 8, 2001

Application No.: To be assigned

Prior Group Art Unit: 2824

Filed: Concurrently Herewith

Prior Examiner: M. Luhrs

For: METHOD OF FORMING NON-
VOLATILE RESISTANCE VARIABLE
DEVICES, METHOD OF PRECLUDING
DIFFUSION OF A METAL INTO
ADJACENT CHALCOGENIDE
MATERIAL, AND NON-VOLATILE
RESISTANCE VARIABLE DEVICE

INFORMATION DISCLOSURE STATEMENT (IDS)

Commissioner for Patents
Washington, DC 20231

Dear Sir:

Pursuant to 37 CFR 1.56, the attention of the Patent and Trademark Office is hereby directed to the references listed on the attached PTO/SB/08. It is respectfully requested that the information be expressly considered during the prosecution of this application, and that the references be made of record therein and appear among the "References Cited" on any patent to issue therefrom.

The references cited in the attached form PTO/SB/08 are not supplied herewith because they were previously cited by or submitted to the Office in U. S.

Patent Application No. 09/779,983, filed February 8, 2001, which is relied upon in this application for an earlier filing date under 35 U.S.C. 120.

Documents discussed in Appendix A marked with an asterisk (*) are indicated to be potentially more relevant than others. Such marking is provided only to assist the Examiner; however, the Examiner is requested to thoroughly review all documents cited herein.

The attention of the Patent and Trademark Office is hereby also directed to pending U.S. Application Serial Nos. 10/077,867, filed February, 2002; 10/230,189, filed August 29, 2002; 10/120,521, filed April 12, 2002; and 09/803,176, filed March 7, 2001. All of these relate to similar subject matter to that described and claimed in the present application. The Examiner is requested to review these applications for any information therein which may be deemed material to the present application.

In accordance with 37 C.F.R. § 1.97(g), the filing of this Information Disclosure Statement shall not be construed to mean that a search has been made or that no other material information as defined in 37 C.F.R. § 1.56(a) exists. It is submitted that the Information Disclosure Statement is in compliance with 37 C.F.R. § 1.98 and the Examiner is respectfully requested to consider and cite the listed documents.

While the information and references disclosed in this Information Disclosure Statement may be “material” pursuant to 37 CFR 1.56, it is not intended to constitute an admission that any patent, publication or other information referred to therein is “prior art” for this invention unless specifically designated as such.

The Commissioner is hereby authorized to charge any deficiency in the fees filed, asserted to be filed or which should have been filed herewith (or with any paper hereafter filed in this application by this firm) to our Deposit Account No. 04-1073, under Order No. M4065.0693/P693-A.

Application No.: To be assigned

Docket No.: M4065.0693/P693-A

Dated: September 12, 2003

Respectfully submitted,

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APPENDIX A

*Kozicki, U.S. Patent No. 6,487,106 (2002): this patent discloses two embodiments shown in Figs. 2 and 3 which include a barrier layer 250, 350, respectively, formed between the layer of conductive material (such as chalcogenide material) 240, 340, respectively and the electrode 230, 330, respectively. (See col. 5, lns. 12-24; col. 7, lns. 7-17). Fig. 5 discloses a structure 502 including an amorphous silicon diode 570 formed adjacent to electrode 520, and a contact 560 formed adjacent the amorphous silicon diode 570.

Kozicki et al., U.S. Patent Application Publication No. 2002/0190350: this publication discloses in Figs. 5A, 6, 8 and 9 a structure having a substrate 510, 610, 810, 910; an insulating layer 520, 620, 820, 920; a bottom electrode 530, 630, 830, 930; an ion conductor 540, 640, 840, 940; a dielectric layer 550, 650, 850, 950; and a top electrode 560, 660, 860, 960. Fig. 5B discloses a structure having a bottom electrode 530, an ion conductor 540, an amorphous diode 562, and a top electrode 560.

*Moore et al., U.S. Patent Application Publication No. 2003/0001229: this publication discloses in Fig. 8 a memory cell structure comprising a substrate 12, a dielectric layer 14, a first metal layer 16, a second metal layer 18, a metal-doped chalcogenide layer 27, another dielectric layer 17, an insulating layer 30, and an electrode 32. First metal layer 16 may be made from tungsten (paragraph 20) and the second metal layer 18 may be silver (paragraph 21).

*Moore et al., U.S. Patent Application Publication No. 2002/0127886: this publication discloses in Fig. 6 a memory cell structure comprising a substrate 10, an insulating layer 11, a conductive layer 12, a metal layer 31, a glass material layer 51, and an electrode 61. Conductive layer 12 may be made from tungsten (paragraph 17) and the metal layer 31 may be silver (paragraph 19).

Moore et al., U.S. Patent Application Publication No. 2002/0123170: this publication discloses in Fig. 6 a memory cell structure which includes a substrate 10, an insulating layer 11, a conductive material 12, a dielectric layer 13, a metal ion-laced glass material 51, a layer of metal material 41, and an electrode 61.

*Kozicki, U.S. Patent Application Publication No. 2003/0035314: this publication discloses a barrier layer 250, 350 as shown in Figs. 2 and 3 and discussed in paragraphs 35 and 45, respectively, formed between the layer of conductive material (such as chalcogenide material) 240, 340, respectively and the electrode 230, 330, respectively. Fig. 5 discloses a structure 502 including an amorphous silicon diode 570 formed adjacent to electrode 520, and a contact 560 formed adjacent the amorphous silicon diode 570, as discussed in paragraph 59.

*Kozicki, U.S. Patent Application Publication No. 2003/0035315: paragraph 70 on page 7 and Fig. 1 disclose a contact 165 electrically coupled to electrode 120, and which may be formed of tungsten. Paragraph 82 on page 8 and Fig. 4 disclose a structure 400 including an amorphous silicon diode 470 formed adjacent to electrode 420, and a contact 460 formed adjacent the amorphous silicon diode 470. Paragraph 102 on page 11 and Figs. 27-28 disclose a common electrode 2710, ion conductors 2730 and 2735, second electrodes 2720 and 2725, and an insulating layer 2750. The insulating layer 2750 is a dielectric layer "that does not interfere with surface electrodeposit growth, such as silicon oxides, silicon nitrides, and the like."

*U.S. Published Applicant No. 2002/0072188 to Gilton: this document generally discloses a programmable variable resistance memory cell in which at least a variable resistance layer of the cell is formed in an isolated stack in an insulative layer.

* U.S. Published Applicant No. 2002/0123169 to Moore et al.: this document discloses a programmable variable resistance memory cell having a first conductive layer 16 formed in an opening in a first dielectric layer, a second conductive layer 18 formed on the first conductive layer. A layer of a chalcogenide material is formed in an opening in a

second dielectric layer aligned with the opening in the first dielectric layer so that the chalcogenide material is formed on and over the first and second conductive layers, and a third conductive layer 32 is formed over the layer of chalcogenide material. *See* paras. 22, 28 and Fig. 8.

* U.S. Published Applicant No. 2002/0123248 to Moore et al.: this document discloses a programmable variable resistance memory cell having a first conductive layer 16 formed in an opening in a first dielectric layer, a second conductive layer 18 formed on the first conductive layer. A layer of a chalcogenide material is formed in an opening in a second dielectric layer aligned with the opening in the first dielectric layer so that the chalcogenide material is formed on and over the first and second conductive layers, and a third conductive layer 32 is formed over the layer of chalcogenide material. *See* paras. 22, 28 and Fig. 8.

* U.S. Published Applicant No. 2002/0168820 to Kozicki: this document discloses several embodiments of a programmable variable resistance memory cell formed in via. An example of the structure disclosed is illustrated in Fig. 1, which shows a first electrode layer 130, a dielectric layer 150 formed on the electrode layer 130 and having an opening formed therethrough to the electrode layer 130, a chalcogenide layer 140 formed in the opening, a barrier layer 155 formed in the opening on the chalcogenide layer 140, a second electrode layer 120 formed in the opening on the barrier layer 155, and a contact layer 165 formed on the second electrode layer 120.

*U.S. Patent No. 6,117,720 to Harshfield: this document generally discloses a plug-type stacked structure for a programmable variable resistance memory cell.

*U.S. Patent No. 6,236,059 to Wolstenholme et al.: this document generally discloses a stacked structure for a programmable variable resistance memory structure 55 partially formed in a pore 50.

*U.S. Patent No. 6,300,684 to Gonzalez et al: this document discloses a programmable variable resistance memory cell 200 formed inside a pore 140, 215 formed in a substrate. *See, e.g.*, Figs. 14-15, col. 6, ln. 81 – col. 7, ln. 34.

*U.S. Patent No. 6,316,784 to Zahorik et al.: this document generally discloses a programmable variable resistance memory cell formed inside pores formed in a substrate.

*U.S. Patent No. 6,348,365 to Moore et al.: this document discloses a programmable variable resistance memory cell which includes a first electrode 12, a chalcogenide –metal ion layer 51, a metal layer 41 which supplies metal ions of the type in the layer 51, and a second electrode 61. *See* Fig. 6.

*U.S. Patent No. 6,391,688 to Gonzalez et al.: this document is a divisional of U.S. Patent No. 6,300,684 and discloses a programmable variable resistance memory cell 200 formed inside a pore 140, 215 formed in a substrate. *See, e.g.*, Figs. 14-15, col. 6, ln. 81 – col. 7, ln. 34.

*WO 00/48196 to Kozicki et al.: this document discloses several embodiments of a programmable variable resistance memory cell formed in via. An example of the structure disclosed is illustrated in Fig. 2, which shows a first electrode layer 230, a dielectric layer formed on the electrode layer 230 and having an opening formed therethrough to the electrode layer 230, a barrier layer 250 formed in the opening and on the first electrode layer 230, a chalcogenide layer 240 formed in the opening on the barrier layer 250, a second electrode layer 220 formed in the opening on the chalcogenide layer 240, and a contact layer formed on the second electrode layer 220.

*WO 02/21542 to Kozicki: this document is the international equivalent to U.S. Published Application No. 2002/0168820 and discloses several embodiments of a programmable variable resistance memory cell formed in via. An example of the structure disclosed is illustrated in Fig. 1, which shows a first electrode layer 130, a dielectric layer 150 formed on the electrode layer 130 and having an opening formed therethrough to the

electrode layer 130, a chalcogenide layer 140 formed in the opening, a barrier layer 155 formed in the opening on the chalcogenide layer 140, a second electrode layer 120 formed in the opening on the barrier layer 155, and a contact layer 165 formed on the second electrode layer 120.

Abdel-All, et al., Vacuum 59 (2000) 845-853: published in December, this document generally relates to, inter alia, the electrical properties of $\text{Ge}_5\text{As}_{38}\text{Te}_{57}$ as a function of temperature.

*Adler and Moss, J. Vac. Sci. Technol. 9 (1972) 1182-1189: this document generally relates to, inter alia, two types of electrical/material switching – threshold and memory, in amorphous materials; the effects of temperature, pressure, and frequency on switching; and the physics of threshold voltage and memory.

Adler et al., Ref. Mod. Phys. 50 (1978) 209-220: this document generally relates to, inter alia, threshold switching in amorphous alloys, state (“on” and “off”) characteristics, and glass properties.

Affi, et al., Appl. Phys. A 55 (1992) 167-169: this document generally relates to, inter alia, SeGe-Sb glasses.

*Affi, et al., J. Phys. 17 (1986) 335-342: this document generally relates to, inter alia, electrical and thermal conductivity of $\text{Ge}_x\text{Se}_{1-x}$ compositions as a function of temperature. $\text{Ge}_{25}\text{Se}_{75}$ stoichiometry is disclosed.

Alekperova and Gadzhieva, 23 (1987) 137-139: this document generally relates to, inter alia, a characteristic diode state in Ag_2Se compositions upon heating (to 376-400°K).

*Aleksiejunas and Cesnys, Phys. Stat. Sol. (a) 19 (1973) K169-K171: this document generally relates to, inter alia, the subjects of selenium investigation and how Se- Ag_2Se contributes silver ions to a selenium composition.

Angell, Annu. Rev. Phys. Chem. 43 (1992) 693-717: this document generally relates to, inter alia, the presence of ion conductors in solids.

Aniya, Solid State Ionics 136-137 (November 2,2000) 1085-1089: this document generally relates to, inter alia, ion conductor glasses.

Asahara and Izumitani, J. Non-Cryst. Solids 11 (1972) 97-104: this document generally relates to, inter alia, Cu-As-Se glass.

Asokan, et al., Phys. Rev. Lett. 62 (1989) 808-810: this document generally relates to, inter alia, $\text{Ge}_x\text{Se}_{100-x}$ glasses and their transition from semiconductor-like material to metal-like material.

Baranovskii and Cordes, J. Chem. Phys. 111 (1999) 7546-7557: this document generally relates to, inter alia, ionic glasses and conduction (percolation theory).

Belin et al., Sol. St. Ionics 136-137 (November 2,2000) 1025-1029: this document generally relates to, inter alia, conductivity spectra of the glass $0.5\text{Ag}_2\text{S}-0.5\text{GeS}_2$ and the temperature dependency of the conductivity.

Belin, et al., Solid State Ionics 143 (July 2,2001) 445-455: this document generally relates to, inter alia, the electrical properties of $\text{Ag}_7\text{GeSe}_5\text{I}$ – an argyrodite compound.

Benmore and Salmon, Phys. Rev. Lett. 73 (1994) 264-267: this document generally relates to, inter alia, the characteristics of chalcogenide alloys.

Bernede, Thin Solid Films 70 (1980) L1-L4: this document is in the French language and the Applicant has no translation. It is presently understood to generally relate to, inter alia, metal- Ag_2Se -metal sandwich devices.

Bernede, Thin Solid Films 81 (1981) 155-160: this document generally relates to, inter alia, memories of selenium alloys with metal (e.g., Ag) electrodes, where the “on” memory states require constant voltage.

Bernede, Phys. Stat. Sol. (a) 57 (1980) K101-K104: this document generally relates to, inter alia, metal-Ag₂Se-P systems.

Bernede and Abachi, Thin Solid Films 131 (1985) L61-L64: this document generally relates to, inter alia, metal-insulator-metal thin films with electroforming effects; the films have silver, gold and copper electrodes.

*Bernede, et al., Thin Solid Films 97 (1982) 165-171: this document generally relates to, inter alia, Ag₂Se/Se/Metal thin film sandwiches, which were studied by shape of electrodes (e.g., symmetrical or asymmetrical).

Bernede, et al., Phys. Stat. Sol. (a) 74 (1982) 217-224: this document generally relates to, inter alia, switching in Al-Al₂O₃Ag_{2-x}Se_{1+x} devices.

Bondarev and Pikhitsa, Solid State Ionics 70/71 (1994) 72-76: this document generally relates to, inter alia, Ag⁽⁺⁾/RbAg₄I₅ boundary – depletion layer, and dendritic electrodeposition.

*Boolchand, Asian Journal of Physics (2000) 9, 709-72: this document generally relates to, inter alia, Ge_xSe_{1-x} glasses, which have selenium-rich and germanium-rich clusters, and the intrinsically-broken bond characteristics thereof.

*Boolchand and Bresser, Nature 410 (2001) 1070-1073: published April 26, this document generally relates to, inter alia, Ag₂Se as an electrolyte additive to glass, e.g., GeSe₄. Ge₃₀Se₇₀ glass was found not to work well because of Ag₂Se crystallization.

*Boolchand, et al., J. Optoelectronics and Advanced Materials, 3 (September 2001), 703: this document generally relates to, inter alia, a review of Raman tool scattering

of chalcogenide glasses. The floppyness and rigidity is observed. $\text{Ge}_x\text{Se}_{1-x}$ is disclosed, as is a stoichiometry of $\text{Ge}_{25}\text{Se}_{75}$.

Boolchand and Grothaus, Eds. Chadi and Harrison, Proc. Int. Conf. Phys, Semicond., 17th (1985) 833-36: this document generally relates to, inter alia, GeSe and GeS glasses and the importance of a broken chemical order therein.

*Boolchand, et al., Properties and Applications of Amorphous Materials, M.F. Thorpe and Tichy, L. (eds.) Kluwer Academic Publishers, the Netherlands, 2001, pp. 97-132: this document generally relates to, inter alia, the prediction of glass rigidity in $\text{Ge}_x\text{Se}_{1-x}$ glass, e.g., $\text{Ge}_{23}\text{Se}_{77}$.

*Boolchand, et al., Diffusion and Defect Data, Vol. 53-54 (1987) 415-420: this document generally relates to, inter alia, thermal annealing of $\text{Ge}_x\text{Se}_{1-x}$ films.

*Boolchand, et al., Phys. Rev. B 25 (1982) 2975-2978: this document generally relates to, inter alia, the examination of GeSe glass having Sn impurities by Mossbauer spectroscopy. Investigations into glass network topology, which has an intrinsically broken bond backbone, suggesting Ge and Se rich clusters.

Boolchand, et al., Sol. State Comm. 45 (1983) 183-185: this document generally relates to, inter alia, $\text{Ge}_x\text{Se}_{1-x}$ and $\text{Ge}_x\text{S}_{1-x}$ glasses.

*Boolchand and Bresser, Dep. Of ECECS, Univ. Cincinnati 45221-0030: this document generally relates to, inter alia, $\text{Ge}_x\text{Se}_{1-x}$ and the relation of glass transition temperature to Ge concentration in backbone. Although the publication date of this reference is not known to the Applicant, it was revised October 28, 1999 and is believed to be publicly available at the University of Cincinnati, Department of Electrical and Computer Engineering and Computer Science.

Bresser, et al., Phys. Rev. Lett. 56 (1986) 2493-2496: this document generally relates to, inter alia, an investigation of c- GeSe_2 structure.

Bresser, et al., J. de Physique 42 (1981) C4-193-C4-196: this document generally relates to, inter alia, the characteristics of GeSe_2 and GeS_2 glasses.

Bresser, et al., Hyperfine Interactions 27 (1986) 389-392: this document generally relates to, inter alia, germanium selenide glasses doped with tellurium.

Cahen, et al., Science 258 (1992) 271-274: this document generally relates to, inter alia, chalcopyrite CuInSe_2 glasses.

Chatterjee, et al., J. Phys. D: Appl. Phys. 27 (1994) 2624-2627: this document generally relates to, inter alia, $\text{As}_x\text{Te}_{100-x-y}\text{Se}_y$ glasses and the current, voltage, and electrical switching behavior. Discloses applicability in read mostly memories.

*Chen and Tai, Appl. Phys. Lett. 37 (1980) 1075-1077: this document generally relates to, inter alia, silver photodoping of $\text{Ge}_x\text{Se}_{1-x}$ and whisker formation (crystalline Ag_2Se).

Chen and Cheng, J. Am. Ceram. Soc. 82 (1999) 2934-2936: this document generally relates to, inter alia, germanium containing chalcogenides doped with Si_3N_4 .

Chen, et al., J. Non-Cryst. Solids 220 (1997) 249-253: this document generally relates to, inter alia, $\text{As}_{10}\text{Ge}_{30}\text{Se}_{60}$ glasses (and the like) doped with Si_3N_4 .

Cohen, et al., J. Non-Cryst. Solids 8-10 (1972) 885-891: this document generally relates to, inter alia, Ge-Te-X glasses as memory devices.

Croitoru, et al., J. Non-Cryst. Solids 8-10 (1972) 781-786: this document generally relates to, inter alia, the physics of conductivity in Ge-containing films.

Dalven and Gill, J. Appl. Phys. 38 (1967) 753-756: this document generally relates to, inter alia, beta- Ag_2Te .

Davis, Search 1 (1970) 152-155: this document generally relates to, inter alia, the subject of amorphous semiconductors as compared to glass.

*Dearnaley, et al., Rep. Prog. Phys. 33 (1970) 1129-1191: this document generally relates to, inter alia, background information about glass and memory.

*Dejus, et al., J. Non-Cryst. Solids 143 (1992) 162-180: this document generally relates to, inter alia, Ag-Ge-Se glass with Ag primarily bonded to Se. The reference discloses glass preparation.

den Boer, Appl. Phys. Lett. 40 (1982) 812-813: this document generally relates to, inter alia, a-Si:H sandwich structures and threshold switching from a low to high conductance.

Drusedau, et al., J. Non-Cryst. Solids 198-200 (1996) 829-832: this document generally relates to, inter alia, work with a-Si:H multilayers optoelectrical properties.

El Bouchairi, et al., Thin Solid Films 110 (1983) 107-113: this document generally relates to, inter alia, $\text{Ag}_{2-x}\text{Se}_{1+x}$ thin film electrical characteristics and metal-like conduction.

El Gharras, et al., J. Non-Cryst. Solids 155 (1993) 171-179: this document generally relates to, inter alia, photoconductivity of amorphous Se and Ge-Se alloy evaporated films, and reduction of photocurrent by increase of Ge content.

*El Ghrandi, et al., Thin Solid Films 218 (1992) 259-273: this document generally relates to, inter alia, GeSe films deposited by PECVD, Ag evaporation deposition onto glass and photodissolution into same, and optical properties are investigated. GeSe stoichiometries of 30/70 and 25/75, respectively, are disclosed.

*El Ghrandi, et al., Phys. Stat. Sol. (a) 123 (1991) 451-460: this document generally relates to, inter alia, dissolution of Ag into $\text{GeSe}_{5.5}$ glass by flash evaporation.

El-kady, Indian J. Phys. 70 A (1996) 507-516: this document generally relates to, inter alia, $\text{Ge}_{21}\text{Se}_{17}\text{Te}_{62}$ glass and memory, switching, and current controlled negative resistance.

Elliott, J. Non-Cryst. Solids 130 (1991) 85-97: this document generally relates to, inter alia, mechanisms of photodissolution of metals (e.g., Ag) in chalcogenides based on ionic and electronic charge carriers.

*Elliott, J. Non-Cryst. Sol. 130 (1991) 1031-1034: this document generally relates to, inter alia, the photodissolution of metals (e.g., Ag) in chalcogenide glasses and the physics thereof.

Elsamanoudy, et al., Vacuum 46 (1995) 701-707: this document generally relates to, inter alia, studies of quaternary chalcogenide films with Te-As-Ge-Si sandwich structures between electrodes.

*El-Zahed and El-Korashy, Thin Solid Films 376 (November 1,2000) 236-240: this document generally relates to, inter alia, $\text{Ge}_{20}\text{Bi}_x\text{Se}_{80-x}$ film analysis regarding conduction and changes from p to n type.

Fadel, Vacuum 44 (1993) 851-855: this document generally relates to, inter alia, a study of the switching and memory characteristics of $\text{Se}_{75}\text{Ge}_{25-x}\text{As}_x$ films.

*Fadel and El-Shair, Vacuum 43 (1992) 253-257: this document generally relates to, inter alia, $\text{Se}_{75}\text{Ge}_7\text{Sb}_{18}$ glass electrical conduction and thermal character.

Feng, et al., Phys. Rev. Lett. 78 (1997) 4422-4425: this document generally relates to, inter alia, germanium selenide and germanium sulfide materials.

*Feng, et al., J. Non-Cryst. Solids 222 (1997) 137-143: this document generally relates to, inter alia, the structural character of $\text{Ge}_x\text{S}_{1-x}$ glass, e.g., hardness and elasticity.

*Fischer-Colbrie, et al., Phys. Rev. B 38 (1988) 12388-12403: this document generally relates to, inter alia, photodiffused Ag-GeSe₂ and the interaction between doped Ag with Se atoms and Ge with Ge atoms.

Fleury, et al., Phys. Stat. Sol. (a) 64 (1981) 311-316: this document generally relates to, inter alia, amorphous selenium films and their conductance.

Fritzsche, J. Non-Cryst. Sol. 6 (1971) 49-71: this document generally relates to, inter alia, background information on chalcogenides as semiconductors.

Fritzsche, Annual Review of Mat. Sci. 2 (1972) 697-744: this document generally relates to, inter alia, background information on amorphous semiconductors.

Gates, et al., J. Am. Chem. Soc. (2001): this document generally relates to, inter alia, creating Ag₂Se nanowires by chemical reaction.

Gosain, et al., Jap. J. Appl. Phys. 28 (1989) 1013-1018: this document generally relates to, inter alia, germanium telluride glasses sandwiched in electrodes and the physics thereof.

*Guin et al., J. Non-Cryst. Sol. 298 (March 28,2002) 260-269: this document generally relates to, inter alia, germanium selenide (GeSe) glass with low hardness, the mechanical properties of which are investigated. Stoichiometries of the glass are disclosed as being, inter alia, 10/90, 20/80, and 30/70, respectively.

*Guin et al., J. Am. Ceram. Soc. 85 (June 2002) 1545-1552: this document generally relates to, inter alia, germanium selenide glasses and a study of the hardness properties thereof. Glass stoichiometries of 40/60 and 20/80, respectively, are disclosed.

Gupta, J. Non-Cryst. Sol. 3 (1970) 148-154: this document generally relates to, inter alia, switching in chalcogenides.

Haberland and Stiegler, J. Non-Cryst. Solids 8-10 (1972) 408-414: this document generally relates to, inter alia, glasses containing Te, As, Ge, and Si, and pulse sequence and time factors in switching.

Haifz, et al., J. Apply. Phys. 54 (1983) 1950-1954: this document generally relates to, inter alia, As-Se-Cu glasses.

Hajto, et al., Int. J. Electronics 73 (1992) 911-913: this document generally relates to, inter alia, metal/a-Si:H/metal devices.

Hajto, et al., J. Non-Cryst. Solids 266-269 (May 1,2000) 1058-1061: this document generally relates to, inter alia, a-Si:H ion conductors, polarity-dependant digital and analogue memory, and dependency on contact metals.

Hajto, et al., J. Non-Cryst. Solids 198-200 (1996) 825-828: this document generally relates to, inter alia, electroformed V/a-Si:H/Cr devices.

Hajto, et al., Phil. Mag. B 63 (1991) 349-369: this document generally relates to, inter alia, p+ type amorphous Si memory structures with polarity dependent analogue switching.

Hayashi, et al., Japan. J. Appl. Phys. 13 (1974) 1163-1164: this document generally relates to, inter alia, Au-CdS(CdSe)-Au systems and metal-Se-Sn-SnO₂ systems.

*Hegab, et al., Vacuum 45 (1994) 459-462: this document generally relates to, inter alia, Ge₂₀M₇₅Sb₁₈ glass electrical conduction and thermal character.

Hirose and Hirose, J. Appl. Phys. 47 (1976) 2767-2772: this document generally relates to, inter alia, Ag photodoped As₂S₃, polarized switching, and dendrite formation.

Hong and Speyer, J. Non-Cryst. Solids 116 (1990) 191-200: this document generally relates to, inter alia, Cd-Ge-As glass with Ag contacts.

Hosokawa, J. Optoelectronics and Advanced Materials 3 (2001) 199-214: this document generally relates to, inter alia, x-ray scattering experiments on glassy $\text{Ge}_x\text{Se}_{1-x}$.

Hu, et al., J. Non-Cryst. Solids 227-230 (1998) 1187-1191: this document generally relates to, inter alia, a-Si:H with Cr and V electrodes.

Hu, et al., Phil. Mag. B. 74 (1996) 37-50: this document generally relates to, inter alia, a-Si:H glasses doped with Cr and analogue memory.

Hu, et al., Phil. Mag. B 80 (January 1, 2000) 29-43: this document generally relates to, inter alia, a-Si:H films doped with Cr-p+.

Iizima, et al., Solid State Comm. 8 (1970) 153-155: this document generally relates to, inter alia, switching and memory effects in As-Te-I^{1,2} and As-Te-Ge-Si³ glass systems. Thermal breakdown is proposed switching effect.

Ishikawa and Kikuchi, J. Non-Cryst. Solids 35 & 36 (1980) 1061-1066: this document generally relates to, inter alia, Ge_2S_2 films with Ag photodissolved therein.

*Iyetomi, et al., J. Non-Cryst. Solids 262 (February 2000) 135-142: this document generally relates to, inter alia, Ag/Ge/Se glasses as a composite of GeSe_2 and Ag_2Se (a fast ion conductor) and polarizability of Se ions.

Jones and Collins, Thin Solid Films 40 (1977) L15-L18: this document generally relates to, inter alia, switching in Se films and switching back with reverse pulse.

Joullie and Marucchi, Phys. Stat. Sol. (a) 13 (1972) K105-K109: this document generally relates to, inter alia, As_2Se_7 glass.

Joullie and Marucchi, Mat. Res. Bull. 8 (1973) 433-442: this document generally relates to, inter alia, As_2Se_5 film conduction and switching.

Kaplan and Adler, J. Non-Cryst. Solids 8-10 (1972) 538-543: this document generally relates to, inter alia, thermal effects on semiconductor switching.

*Kawaguchi, et al., J. Appl. Phys. 79 (1996) 9096-9104: this document generally relates to, inter alia, Ag-rich chalcogenide glass, $\text{Ge}_3\text{S}_7\text{-Ag}$ and $\text{Ge}_{30}\text{Se}_{70}\text{-Ag}$, max Ag content of 67%, graphs phase diagram, and discloses that Ag works better than Cu.

*Kawaguchi and Masui, Jpn. J. Appl. Phys. 26 (1987) 15-21: this document generally relates to, inter alia, silver photodoping of chalcogenide films, e.g., $\text{Ge}_{30}\text{Se}_{70}$ films.

*Kawasaki, et al., Solid State Ionics 123 (1999) 259-269: this document generally relates to, inter alia, the electrical properties of $\text{Ag}_x(\text{GeSe}_3)_{1-x}$, conductivity EMF measurements, glass composition, X-ray diffraction, T_g and T_c , Ag ion transport, and glass structure.

*Kluge, et al., J. Non-Cryst. Solids 124 (1990) 186-193: this document generally relates to, inter alia, photodiffusion of silver into $\text{Ge}_x\text{Se}_{100-x}$ layers, how this differs from ion beam induced diffusion, $\text{Ge}_{30}\text{Se}_{70}$ stoichiometry, Ag_2Se , and percolation threshold.

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Korkinova and Andreichin, J. Non-Cryst. Solids 194 (1996) 256-259: this document generally relates to, inter alia, polarization of chalcogenide glass as depending on the materials used for electrode contacts.

*Kotkata, et al., Thin Solid Films 240 (1994) 143-146: this document generally relates to, inter alia, GeSe glass switching and film thickness, memory, current filament, chemical and mechanical switching properties, and discloses that heat treatment or aging improves switching.

Lakshminarayan, et al., J. Instn. Electronics & Telecom. Engrs. 27 (1981) 16-19: this document generally relates to, inter alia, tellurium-containing chalcogenide glasses.

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*Leung, et al., Appl. Phys. Lett. 46 (1985) 543-545: this document generally relates to, inter alia, photoinduced diffusion of Ag into $\text{Ge}_x\text{Se}_{1-x}$ and techniques for same.

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*Mitkova, et al., Phys. Rev. Lett. 83 (1999) 3848-3851: this document generally relates to, inter alia, Ag doped chalcogenides, $\text{Ge}_{20}\text{Se}_{80}$ stoichiometry is disclosed, Se rich glasses, Ge rich glasses, stoichiometric glasses, and presence of Ag_2Se .

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*Nang et al., Jap. J. App. Phys. 15 (1976) 849-853: this document generally relates to, inter alia, $\text{Ge}_x\text{Se}_{1-x}$ electrical and optical properties; it also discloses $\text{Ge}_{.80}\text{Se}_{.20}$, $\text{Ge}_{.60}\text{Se}_{.40}$, and $\text{Ge}_{.50}\text{Se}_{.50}$.

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*Neale and Aseltine, , IEEE Transactions On Electron Dev. Ed-20 (1973) 195-209: this document generally relates to, inter alia, read mostly memories with chalcogenides (e.g., Ge, Te), also discloses “floating gate,” and material combinations including Ge and Se.

Ovshinsky and Fritzsche, Metallurgical Transactions 2 (1971) 641-645: this document generally relates to, inter alia, reversible changes in amorphous Si, Be, and B using a laser to write and erase.

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Owen, et al., IEE Proc. 129 (1982) 51-54: this document generally relates to, inter alia, a-Si:H, gold or aluminum dots and silver paste.

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*Owen, et al., Int. J. Electronics 73 (1992) 897-906: this document generally relates to, inter alia, threshold and memory switching a-Si:H ion conductor, polarity-dependant digital memory, analogue memory, and device operation dependency on metal contacts.

Pearson and Miller, App. Phys. Lett. 14 (1969) 280-282: this document generally relates to, inter alia, glass diodes.

*Pinto and Ramanathan, Appl. Phys. Lett. 19 (1971) 221-223: this document generally relates to, inter alia, electric field inducement of glass switching “filamentary” path.

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*Prakash, et al., J. Phys. D: Appl. Phys. 29 (1996) 2004-2008: this document generally relates to, inter alia, switching of $\text{Ge}_{10}\text{As}_{45}\text{Te}_{45}$ glass, study of threshold voltage concept and switch back to off, suitability for read mostly memory.

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*Ramesh, et al., Appl. Phys. A 69 (1999) 421-425: this document generally relates to, inter alia, electrical switching in GeTe with Ag or Cu and thermal character investigations.

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*Sharma, Ind. J. Of Pure and Applied Phys. 35 (1997) 424-427: this document generally relates to, inter alia, n-type Ag_2Se and other material stoichiometries. The device conductivity is analyzed, as is the grain size as a factor in device ability to polarize.

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*Thornburg, J. Elect. Mat. 2 (1973) 3-15: this document generally relates to, inter alia, division of chalcogenides into stoichiometric compounds with no changes upon crystallization, stoichiometric compounds with changes upon crystallization, and non-stoichiometric which phase separate on crystallization, As₂Se, and filament growth as a function of bias applied.

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*Thornburg and White, (1972) 4609-4612: this document generally relates to, inter alia, precipitation of As particles out of As₂Se₃ glass and the alignment in a filament.

*Tichy and Ticha, J. Non-Cryst. Solids 261 (2000) 277-281: published in January, this document generally relates to, inter alia, Ge_xSe_{1-x} glass forming ability and 20/80 respective stoichiometry.

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*West, et al., J. Electrochem. Soc. 145 (1998) 2971-2974: this document generally relates to, inter alia, $\text{Ag}/\text{As}_{24}\text{S}_{36}\text{Ag}_{40}/\text{Ag}$ systems and Ag transport.

*West, Ph.D. Dissertation, ASU 1998: this document generally relates to, inter alia, metal dendrite memory with Ag or Cu doped solid electrolyte, photodissolution of Ag into As_2S_3 glass, lateral devices with silver electrodes, vertical devices with Ag electrodes,

write voltages and lesser read voltages, and pinpoint electrode surrounded by ring electrode. In particular, pages 12-18 of this document discusses the fabrication of horizontal and vertical structures for memory cells which incorporate the electrolyte doped memory material. Although the exact publication date for this document is not known, it is believed to be available at Arizona State University.

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*Helbert et al., SPIE Vol. 333 Submicron Lithography (1982): this publication generally relates to, inter alia, hybrid ultragraphic process using both electron beam and conventional optical exposure within the same device level with a photoresist.

*Kozicki et al., Superlattices and Microstructures, 27 (2000): this publication generally relates to, inter alia, solid solutions of metals (e.g., silver) in arsenic trisulfide and their physical and electrical characteristics.

*Kozicki et al., Microelectronic Engineering, vol. 63/1-3 (2002): this publication generally relates to, inter alia, the photodiffusion of Ag into germanium selenide glass films, the amount of Ag that can be incorporated in to such a film by photodiffusion, and the characteristics of the resulting doped films.

*Kozicki et al., Proceedings of the 1999 Symposium on Solid State Ionic Devices (1999): this publication generally relates to, inter alia, physical and electrical characteristics of metal doped chalcogenide films (photodoped $\text{Ag}_4\text{As}_2\text{S}_3$) between electrodes, useful in memories, configurable connections, and self-repairing interconnections.

*Kozicki and Mitkova, Proceedings of the XIX International Congress on Glass, Society for Glass Technology (2001): this publication generally relates to, inter alia, the physical effects of introduction of Ag into chalcogenide glasses, where introduction is by photodiffusion.

*Kozicki, U.S. Patent No. 6,487,106 (2002): this patent discloses two embodiments shown in Figs. 2 and 3 which include a barrier layer 250, 350, respectively, formed between the layer of conductive material (such as chalcogenide material) 240, 340, respectively and the electrode 230, 330, respectively. (See col. 5, lns. 12-24; col. 7, lns. 7-17). Fig. 5 discloses a structure 502 including an amorphous silicon diode 570 formed adjacent to electrode 520, and a contact 560 formed adjacent the amorphous silicon diode 570.

*Kozicki, U.S. Patent Application Publication No. 2003/0035314: this publication discloses a barrier layer 250, 350 as shown in Figs. 2 and 3 and discussed in paragraphs 35 and 45, respectively, formed between the layer of conductive material (such as chalcogenide material) 240, 340, respectively and the electrode 230, 330, respectively. Fig. 5 discloses a structure 502 including an amorphous silicon diode 570 formed adjacent to electrode 520, and a contact 560 formed adjacent the amorphous silicon diode 570, as discussed in paragraph 59.

*Kozicki, U.S. Patent Application Publication No. 2003/0035315: paragraph 70 on page 7 and Fig. 1 disclose a contact 165 electrically coupled to electrode 120, and which may be formed of tungsten. Paragraph 82 on page 8 and Fig. 4 disclose a structure 400 including an amorphous silicon diode 470 formed adjacent to electrode 420, and a contact 460 formed adjacent the amorphous silicon diode 470. Paragraph 102 on page 11 and Figs. 27-28 disclose a common electrode 2710, ion conductors 2730 and 2735, second electrodes 2720 and 2725, and an insulating layer 2750. The insulating layer 2750 is a dielectric layer "that does not interfere with surface electrodeposit growth, such as silicon oxides, silicon nitrides, and the like."

*Helbert et al., SPIE Vol. 333 Submicron Lithography (1982): this publication generally relates to, inter alia, hybrid ultragraphic process using both electron beam and conventional optical exposure within the same device level with a photoresist.

*Kozicki et al., Superlattices and Microstructures, 27 (2000): this publication generally relates to, inter alia, solid solutions of metals (e.g., silver) in arsenic trisulfide and their physical and electrical characteristics.

*Kozicki et al., Microelectronic Engineering, vol. 63/1-3 (2002): this publication generally relates to, inter alia, the photodiffusion of Ag into germanium selenide glass films, the amount of Ag that can be incorporated in to such a film by photodiffusion, and the characteristics of the resulting doped films.

*Kozicki et al., Proceedings of the 1999 Symposium on Solid State Ionic Devices (1999): this publication generally relates to, inter alia, physical and electrical characteristics of metal doped chalcogenide films (photodoped $\text{Ag}_4\text{As}_2\text{S}_3$) between electrodes, useful in memories, configurable connections, and self-repairing interconnections.

*Kozicki and Mitkova, Proceedings of the XIX International Congress on Glass, Society for Glass Technology (2001): this publication generally relates to, inter alia, the physical effects of introduction of Ag into chalcogenide glasses, where introduction is by photodiffusion.

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| | | | | Application Number | To be assigned |
| | | | | Filing Date | Currently Herewith |
| | | | | First Named Inventor | John T. Moore |
| | | | | Art Unit | 2824 |
| | | | | Examiner Name | M. Luhrs |
| Sheet | 1 | of | 10 | Attorney Docket Number | M4065.0693/P693-A |

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| | | | Application Number | To be assigned | |
| | | | Filing Date | Currently Herewith | |
| | | | First Named Inventor | John T. Moore | |
| | | | Prior Group Art Unit | 2824 | |
| | | | Prior Examiner Name | M. Luhrs | |
| Sheet | 3 | of | 10 | Attorney Docket Number | M4065.0693/P693-A |

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| | | | | First Named Inventor | John T. Moore |
| | | | | Prior Group Art Unit | 2824 |
| | | | | Prior Examiner Name | M. Luhrs |
| Sheet | 9 | of | 10 | Attorney Docket Number | M4065.0693/P693-A |

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| | | | | First Named Inventor | John T. Moore |
| | | | | Prior Group Art Unit | 2824 |
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